



INTERNATIONAL ATOMIC ENERGY AGENCY
UNITED NATIONS EDUCATIONAL, SCIENTIFIC AND CULTURAL ORGANIZATION



INTERNATIONAL CENTRE FOR THEORETICAL PHYSICS
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**EXPERIMENTAL WORKSHOP ON HIGH TEMPERATURE
SUPERCONDUCTORS & RELATED MATERIALS
(BASIC ACTIVITIES)**

12 - 30 MARCH 1990

THIN FILMS

WERNER SCHINDLER

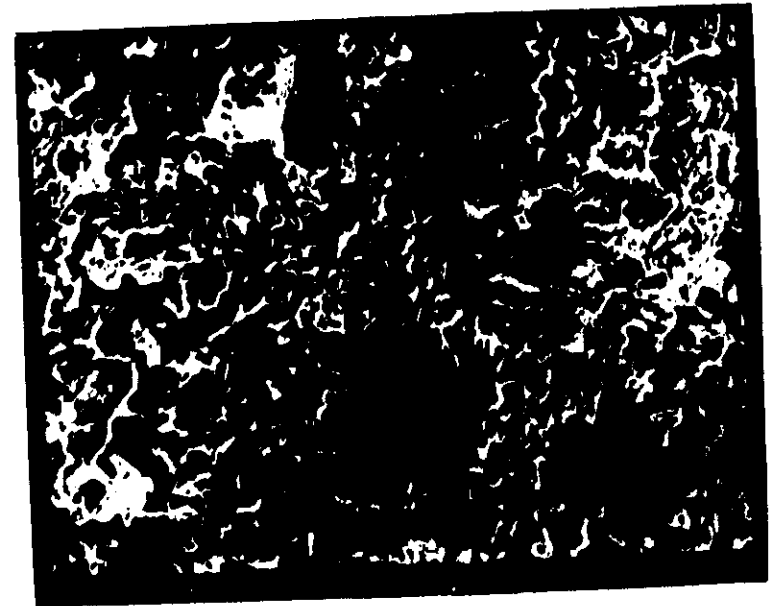
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These are preliminary lecture notes, intended only for distribution to participants.

Thin Films

W. Schindler

Physikalisches Institut
Universität Erlangen



General problems:

- strong anisotropy of electrical parameters
- grain boundaries (weak links)

Dimos - experiment



→ bulk material: poor critical current density
 ($\approx 10^3 \text{ A/cm}^2$ at 77K and $B=0T$)
 textured material: up to $2 \cdot 10^4 \text{ A/cm}^2$

single crystals

or

epitaxial thin films

↑
technical choice

D. Dimos, P. Choudhary, J. Manhart, and F.K. LeGoues
 Phys. Rev. Lett. 61, 219 (1988)

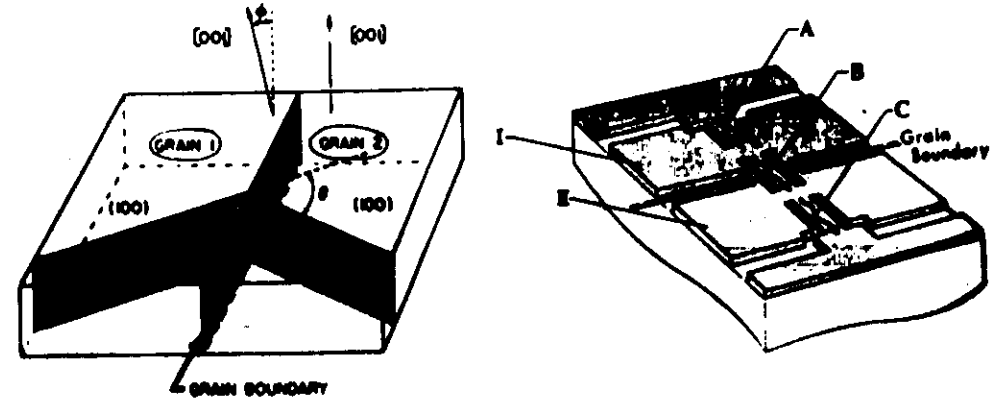
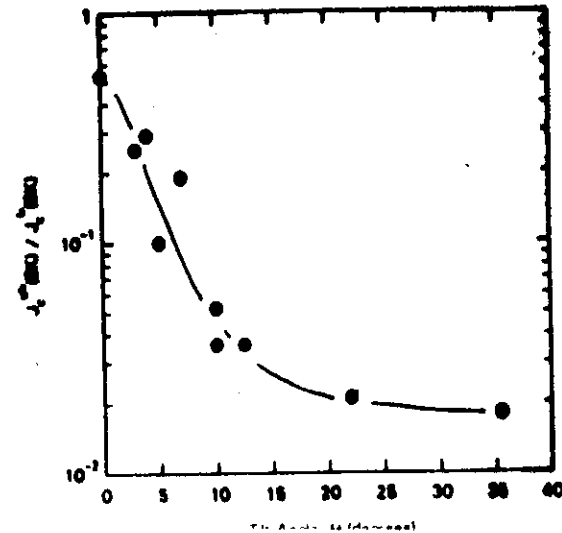
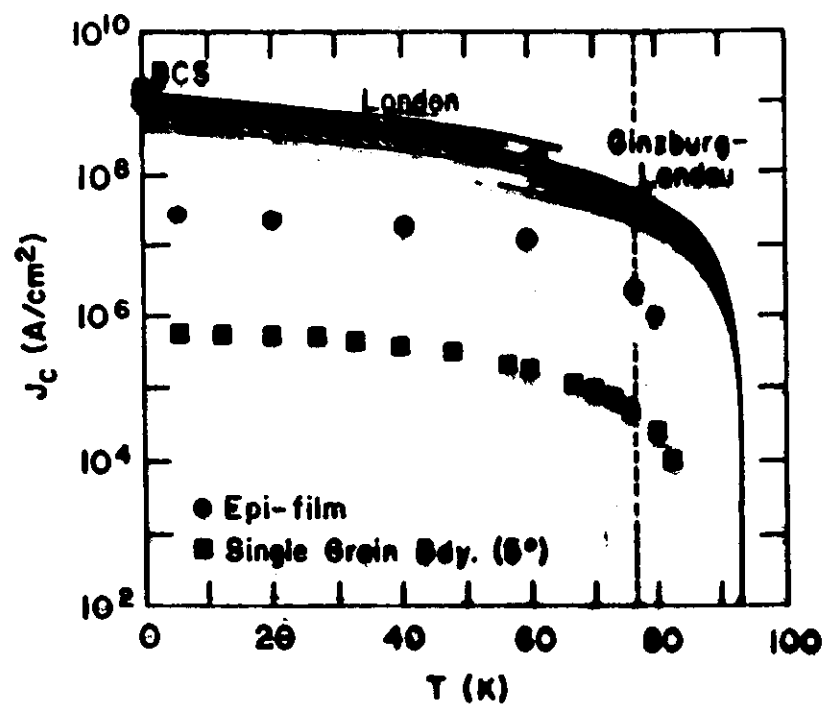


TABLE I. Critical current density (10^3 A/cm^2) at 4.2-5 K.

θ ($^\circ$)	Grain 1	Grain 2	Grain Boundary
0° (3°)	7100	2000	4000
3° (7°)	5900	1300	1400
4° (4°)	270	220	73
5° (9°)	6000	5700	500
7° (4°)	140	180	40
10° (6°)	7000	2000	410
10° (4°)	7000	6100	340
12.5° (2°)	3000	3400	100
22° (2°)	800	200	11
35.5° (4°)	1350	1400	25



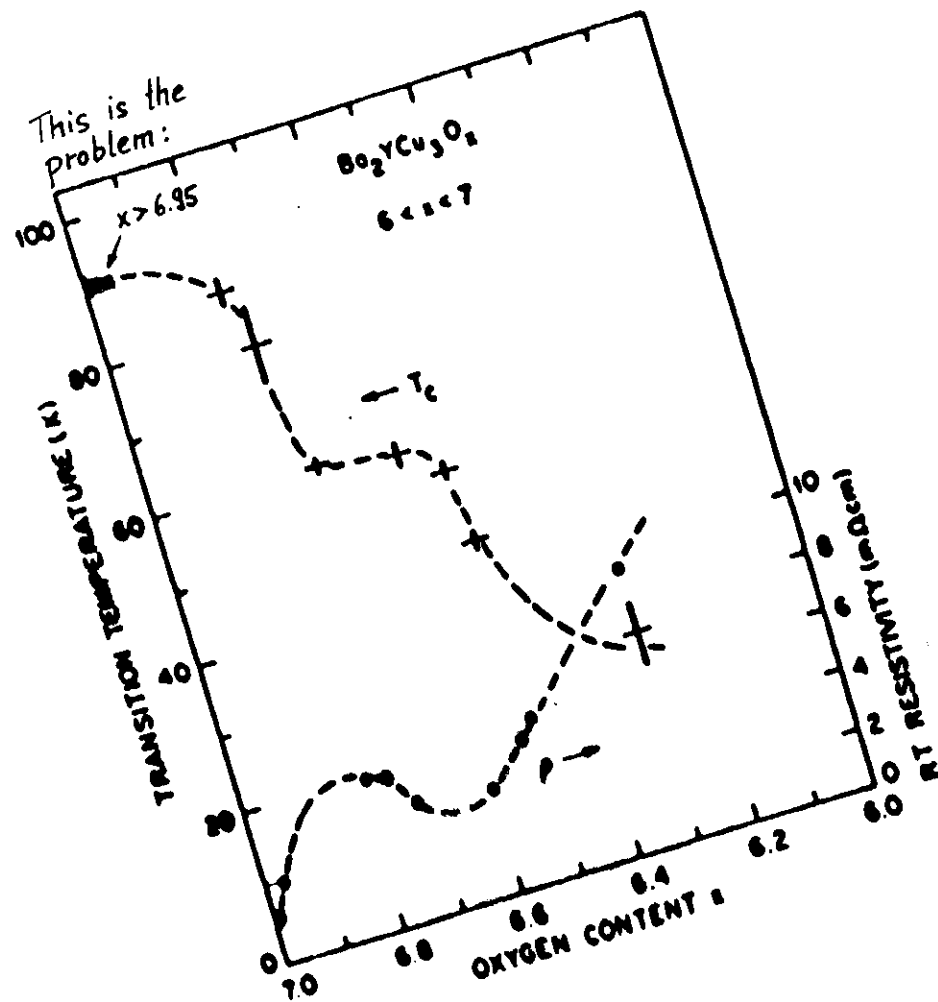


Deposition Methods:

- rf/dc - sputtering
- electron beam evaporation
- Molecular beam epitaxy (MBE)
- Laser ablation
- Chemical vapour deposition (CVD)
- and other methods ...

In principle not possible to grow $\text{YBa}_2\text{Cu}_3\text{O}_{6+x}$ by nearly all thin film deposition methods

↑
tetragonal phase, growth on substrates with



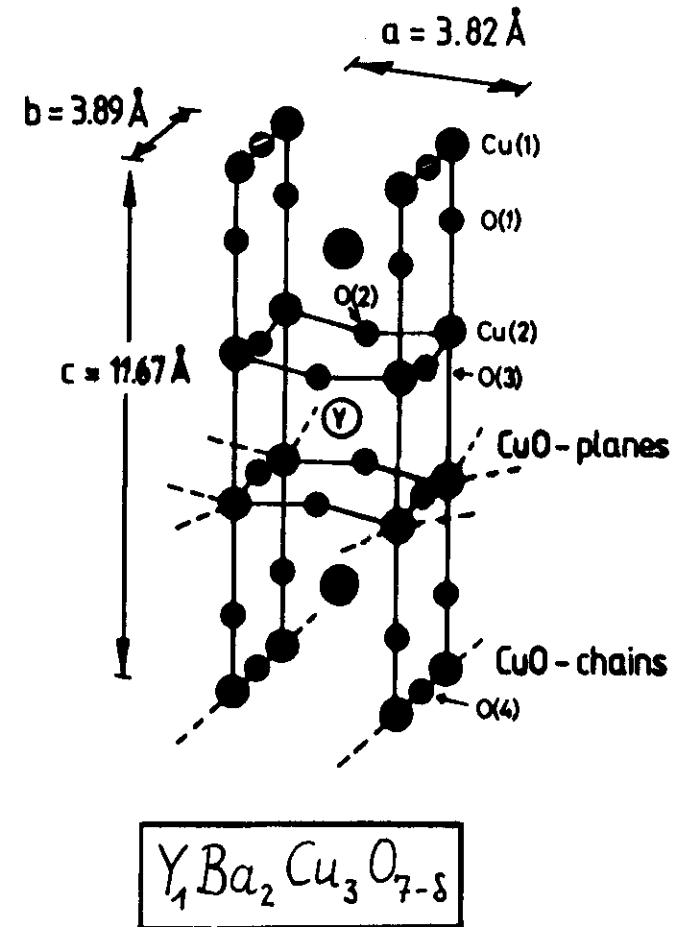
3-step process:

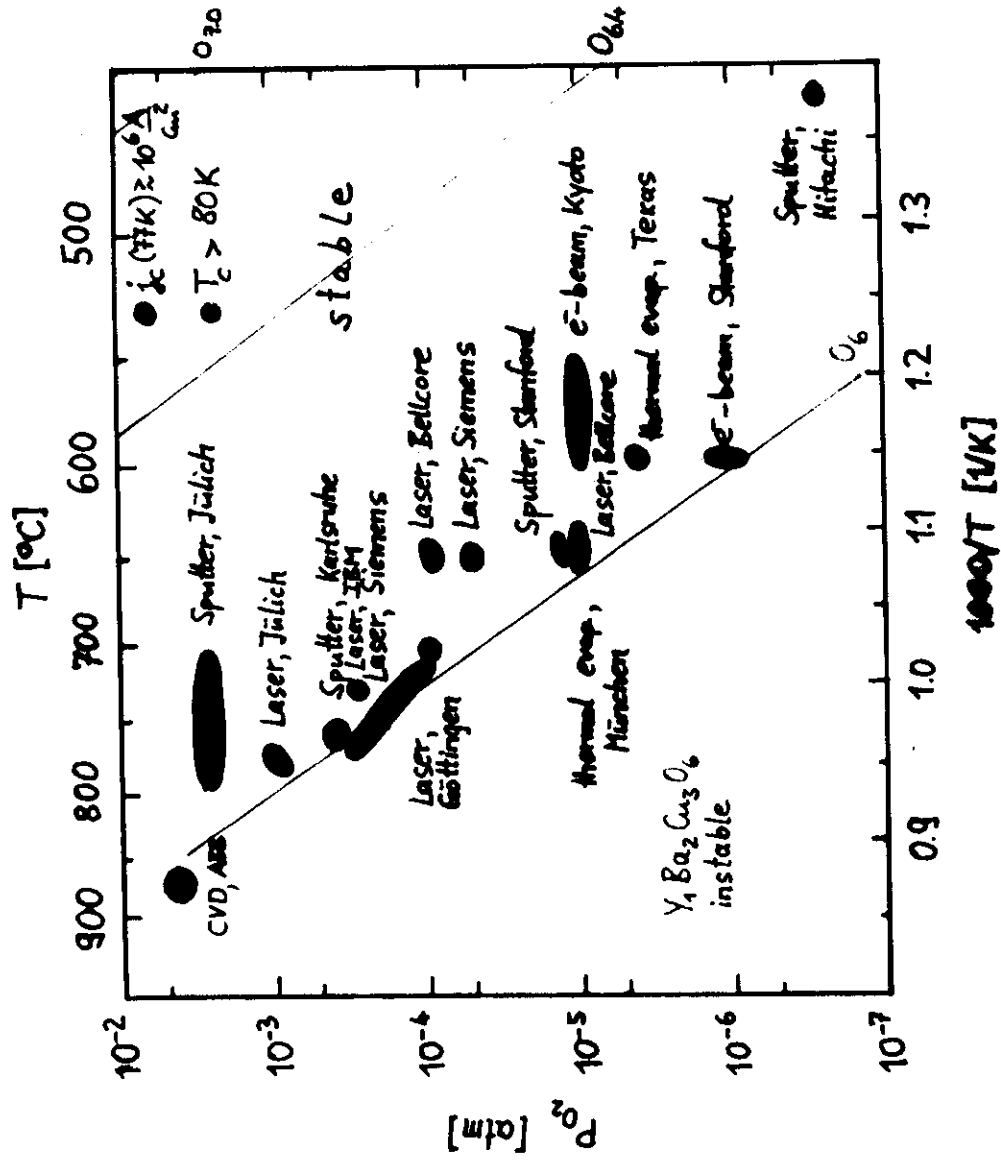
- deposition of the elements
(amorphous film)
- crystallization to tetragonal structure
(ex situ, $T > 900^\circ\text{C}$ in 1 bar O_2)
- phase transformation
tetragonal $\rightarrow$ orthorhombic
(slow cooling in 1 bar O_2)

2-step process: (better way)

- deposition at $600^\circ\text{C} - 750^\circ\text{C}$ in
oxygen partial pressure
(epitaxial growth of tetragonal phase)
- phase transformation
tetragonal $\rightarrow$ orthorhombic
(slow cooling in 1 bar O_2)

All methods work with the 2-step process.

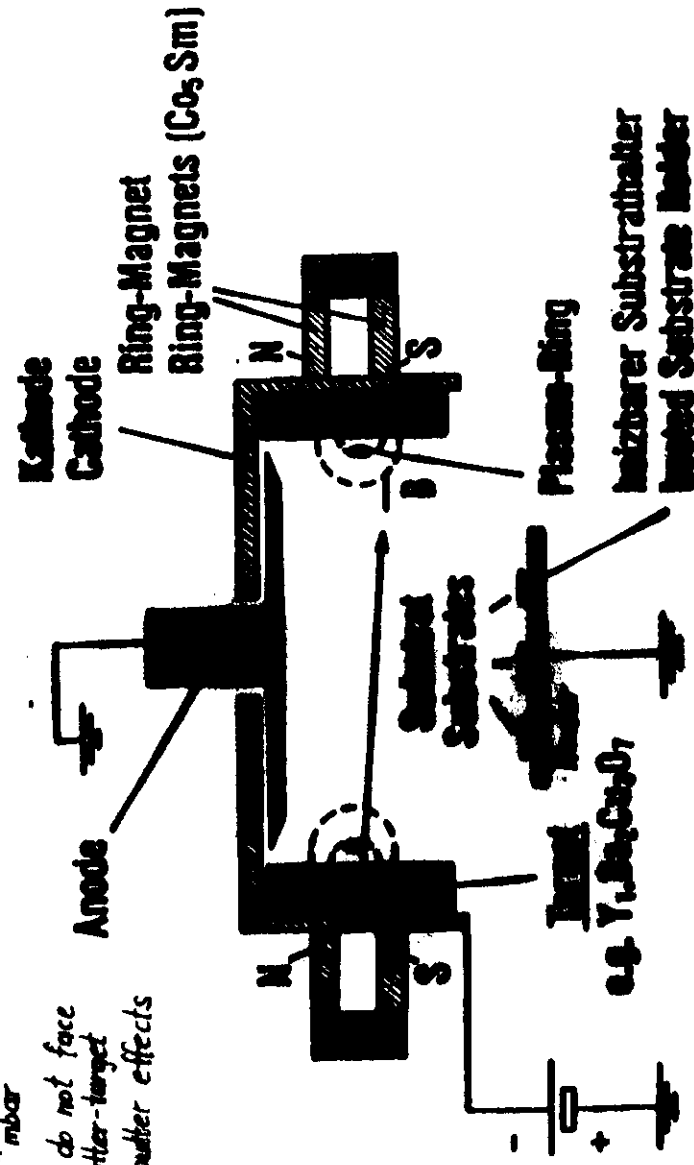




DC-Sputtering

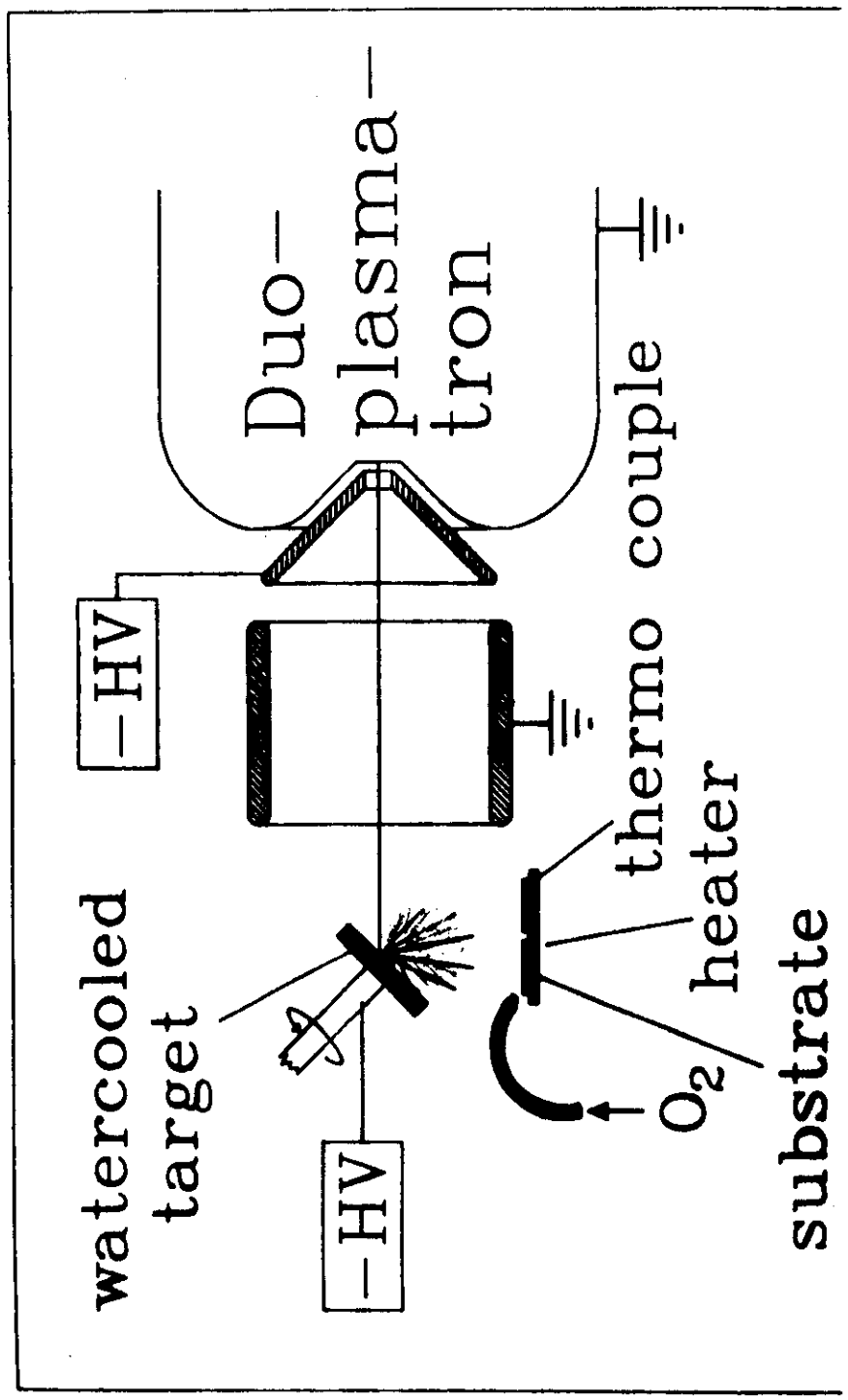
Composite target
 DC-voltage 120 - 180V
 $p_{O_2} \approx 5 \cdot 10^{-4}$ mbar
 substrates do not face
 the sputter-target
 → no re-sputter effects

for example: J. Geerk, G. Linker, G. Meyer
 Kernforschungszentrum Karlsruhe



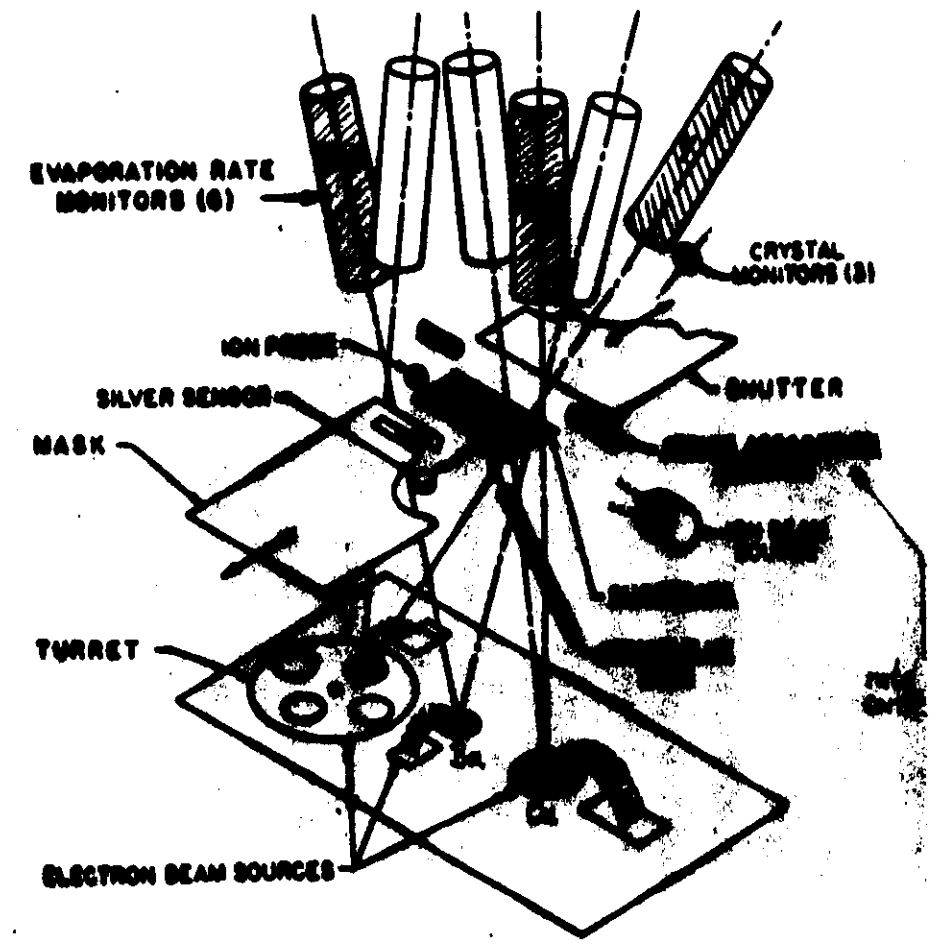
substrates outside of discharge

Primary beam $I = 10 \text{ mA}$ Argon Focusing solenoid
 (D.P. Res.) $\approx 20 \text{ mm}$ $\text{Nd}_{0.15}\text{Fe}_{0.85}$ $\text{In}_{0.15}\text{Ga}_{0.85}$
 Alky $= 20 \text{ Å/mm}$ Film cooled in RT $\approx 20 \text{ cm}$



Electron Beam Evaporation

for ex.: N. Missert, R. Hammond, J.E. Muij, V. Matijasevic, P. Rosenthal, T.H. Geballe,
 A. Kapitulnik, M.R. Beasley
 Stanford University

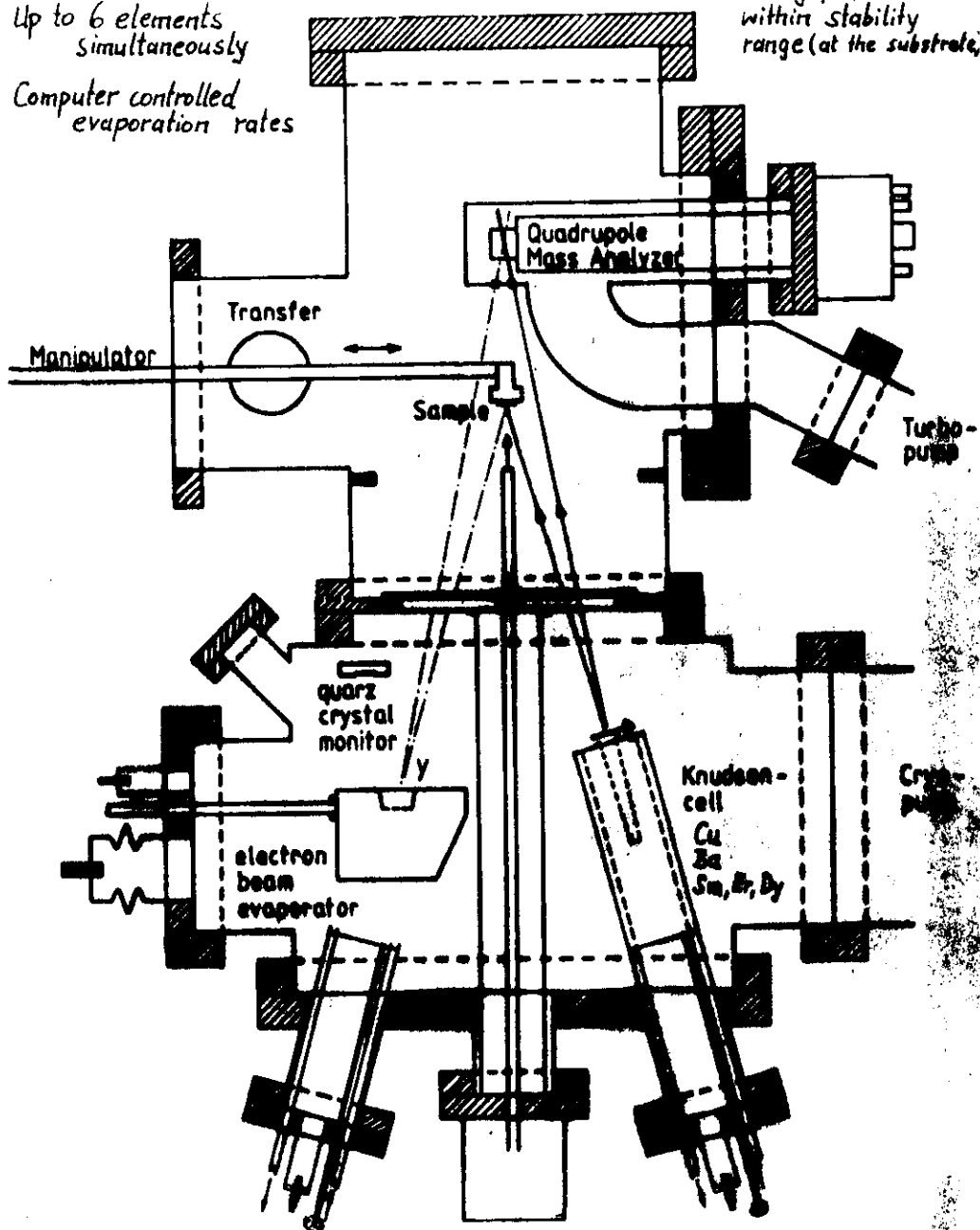


$$P_{O_2} \leq 2 \cdot 10^{-4} \text{ mbar}$$

MBE - CHAMBER

Base pressure $\leq 10^{-10}$ mbar
Up to 6 elements simultaneously
Computer controlled evaporation rates

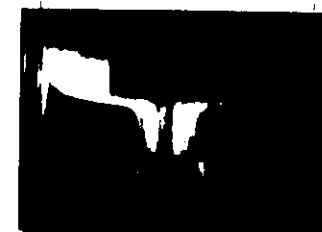
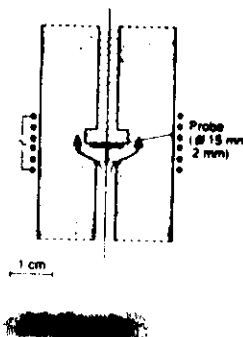
Oxygen pressure during preparation within stability range (at the substrate)



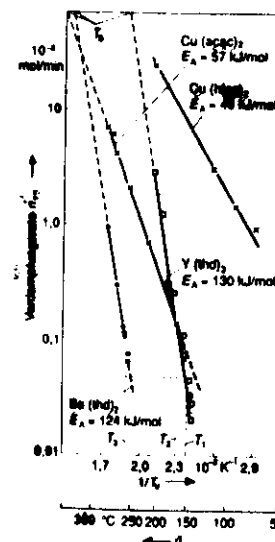
$P_{O_2} \leq 10^{-5}$ mbar

Oxygen ion Source or atomic oxygen source

Chemische Abscheidung von $YBa_2Cu_3O_{7-x}$ aus der Gasphase



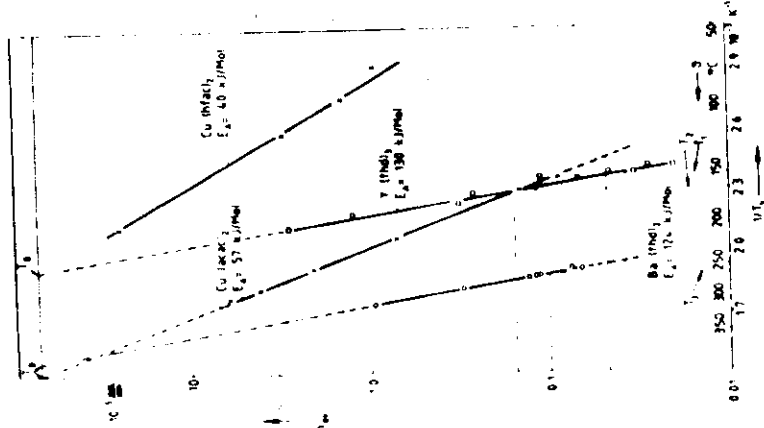
Gasfluß im CVD-Reaktor (70 l/h)



Verdampfungsraten der für die Abscheidung verwendeten Ausgangsmaterialien

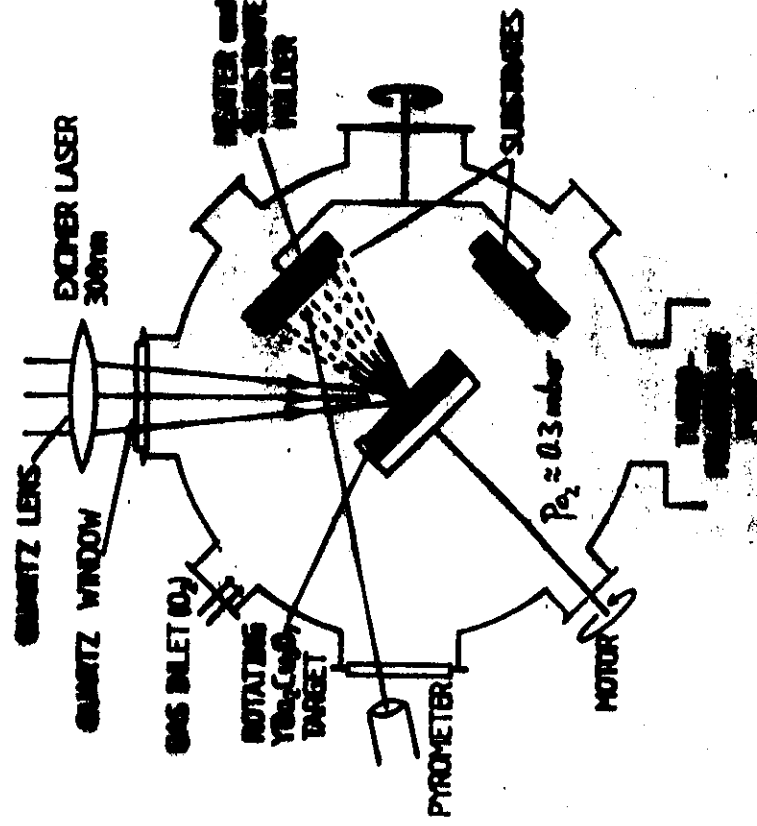


SEM-pictures of $YBa_2Cu_3O_{7-x}$ on YSZ-substrates



Molar evaporation rates $\dot{n}_v$ of Cu(hfac)_2 , Cu(hfac)_2 , Ba(thd)_2 and Y(thd)_3 versus the reciprocal, absolute evaporation temperature $1/T$, $\dot{n}_v = 25 \text{ l/h (STP)}$. Plot - 500 Pa, T_1 , T_2 and T_3 indicates the vaporization temperatures for Y(thd)_3 , Ba(thd)_2 and Cu(hfac)_2 used of the deposition experiments).

for example: B. Roes, Universität Erlangen
L. Schulte, Siemens AG, Erlangen
Appl. Phys. Lett. **53**, 1557 (1988)



LASER Siemens XP 2020 XeCl

- wavelength: 308nm
- pulses: 1 - 2 Joules/100 ns
- repetition rate 5 Hz

TARGET

- sintered $\text{YBa}_2\text{Cu}_3\text{O}_{7-x}$ - pellet
- energy density: 4 Joules/cm²

FILM GROWTH CONDITIONS

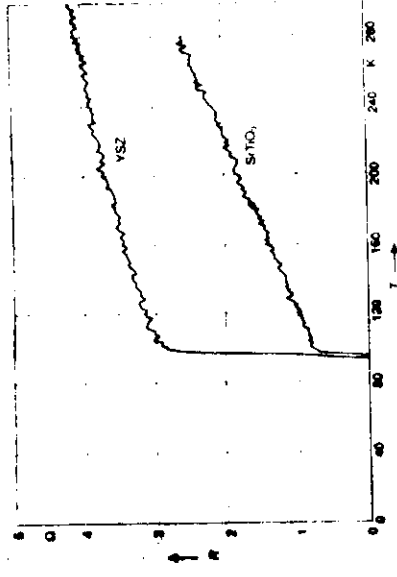
- substrate temperature: 700°C - 800°C
- oxygen pressure: 0.2 mbar - 0.5 mbar
- single crystalline substrates (SrTiO_3 , MgO , LaGaO_3)
- cooling in 1 bar O_2

advantages:

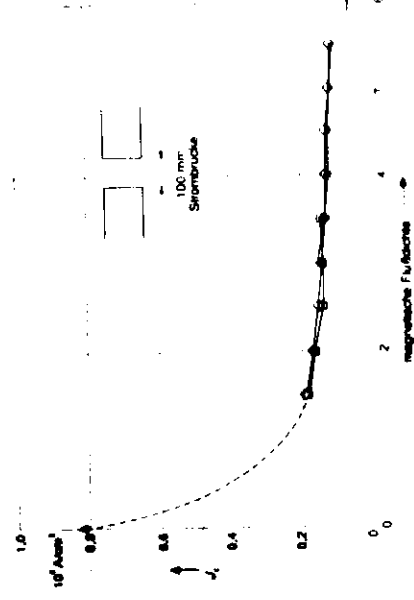
- short preparation times
- high oxygen pressure possible
- conservation of stoichiometry

disadvantages:

- Surface roughness
- particles on film surface
- Small range of homogeneous growth rates

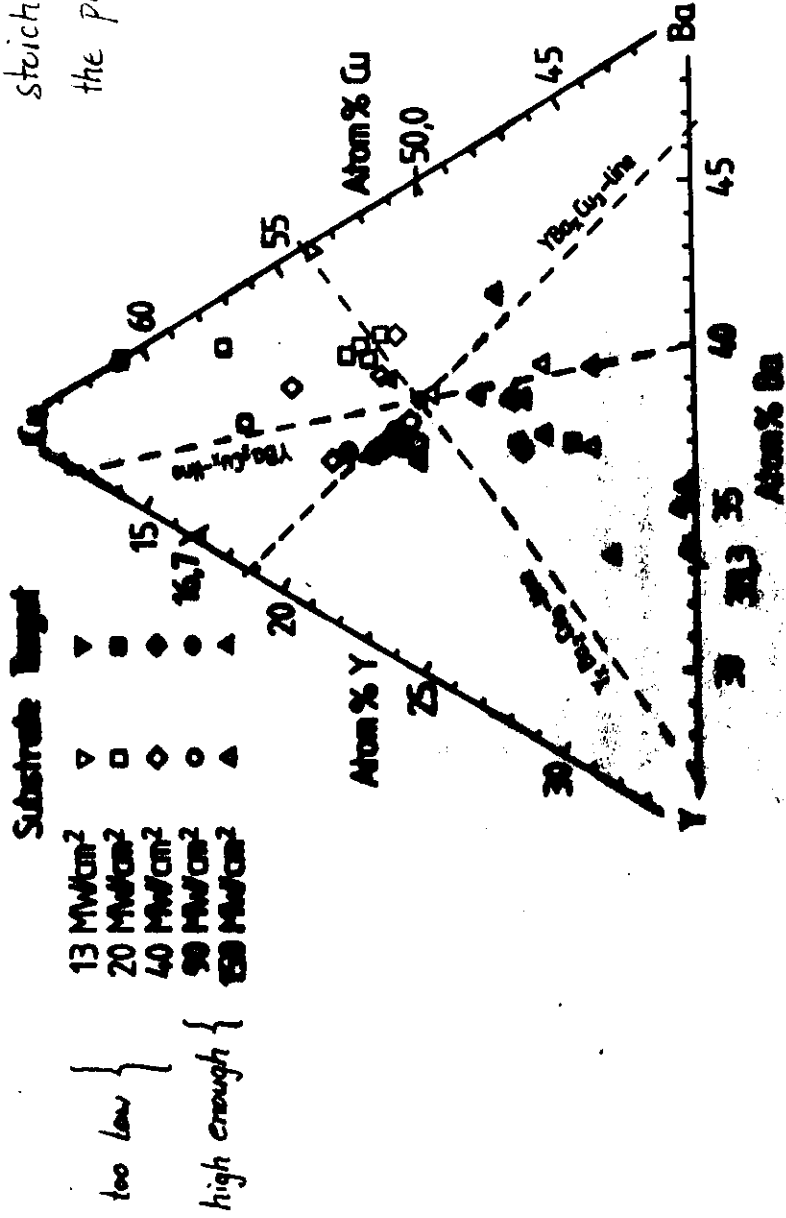


Intensity of laser light Cu(hfac)_2 and $\text{YBa}_2\text{Cu}_3\text{O}_{7-x}$



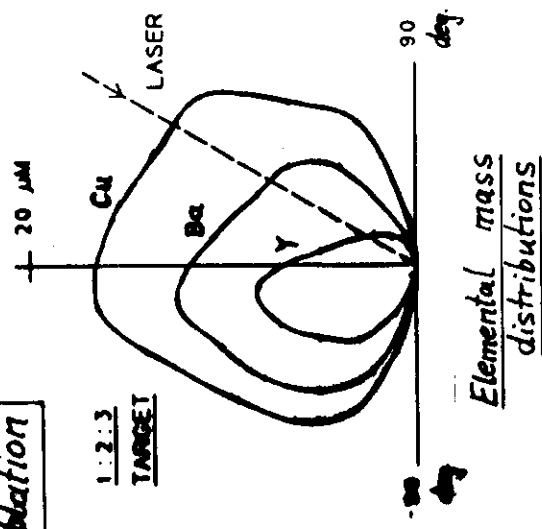
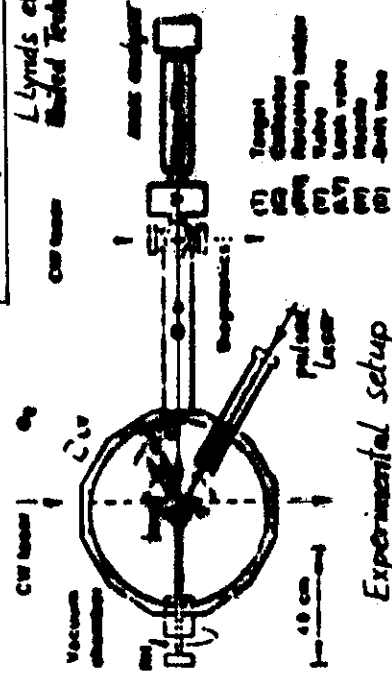
Intensity of laser light Cu(hfac)_2 and $\text{YBa}_2\text{Cu}_3\text{O}_{7-x}$ on SiO_2 substrate

Dependence of
stoichiometry on
the pulse power:

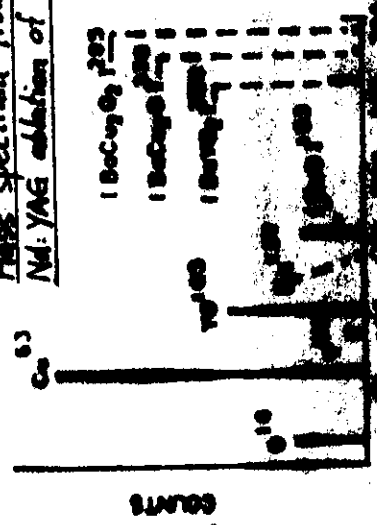


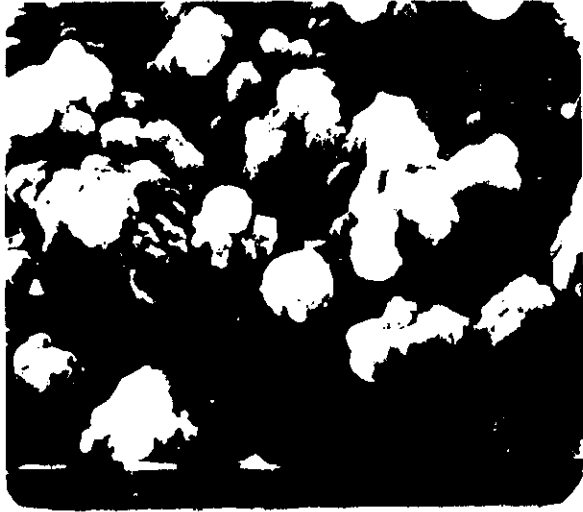
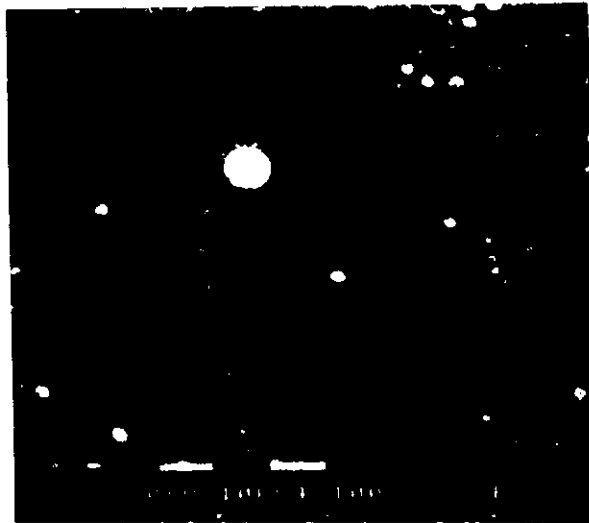
Time Physics of Pulsed Laser Ablation

Llyrds et al.
United Technologies Research Centre

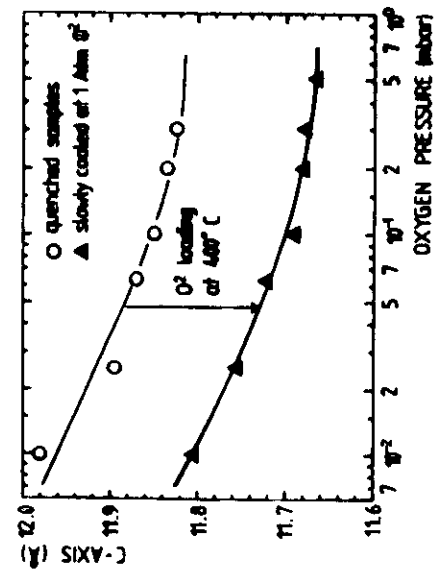


Mass spectrum from
Nd:YAG ablation of 123-target

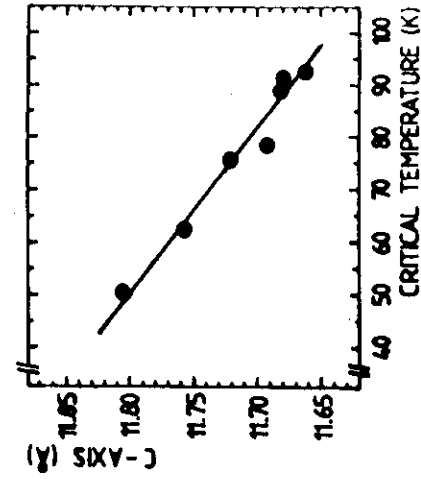




Morphologie der Filme in Abhängig-
keit der Laserwellenlänge
(oben: 1064 nm, unten: 266 nm).

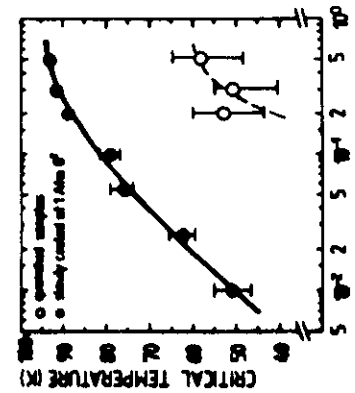


oxygen pressure

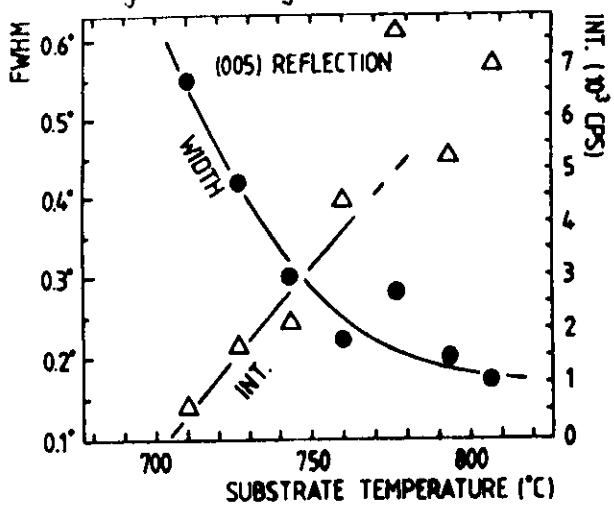


critical temperature

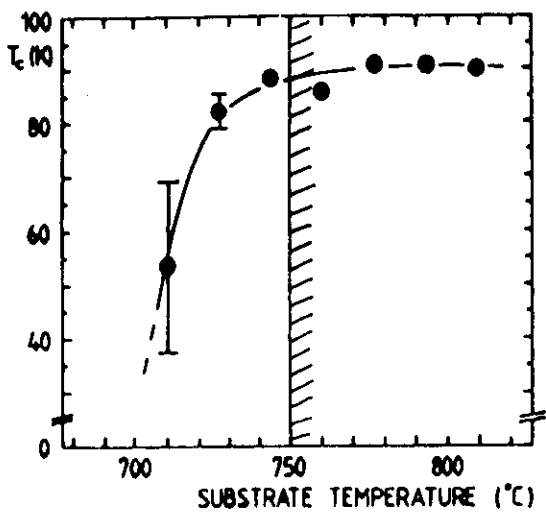
Influence of oxygen pressure



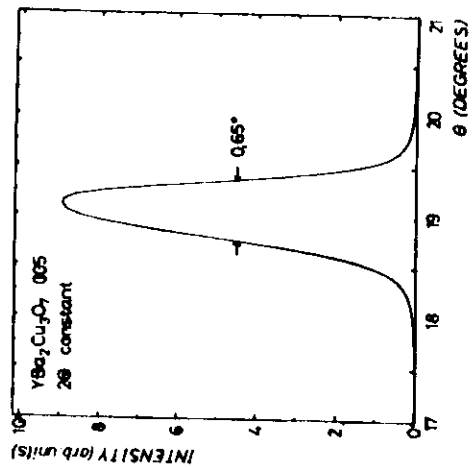
Crystallinity:



Influence of substrate temperature.



! substrate temperature too high:

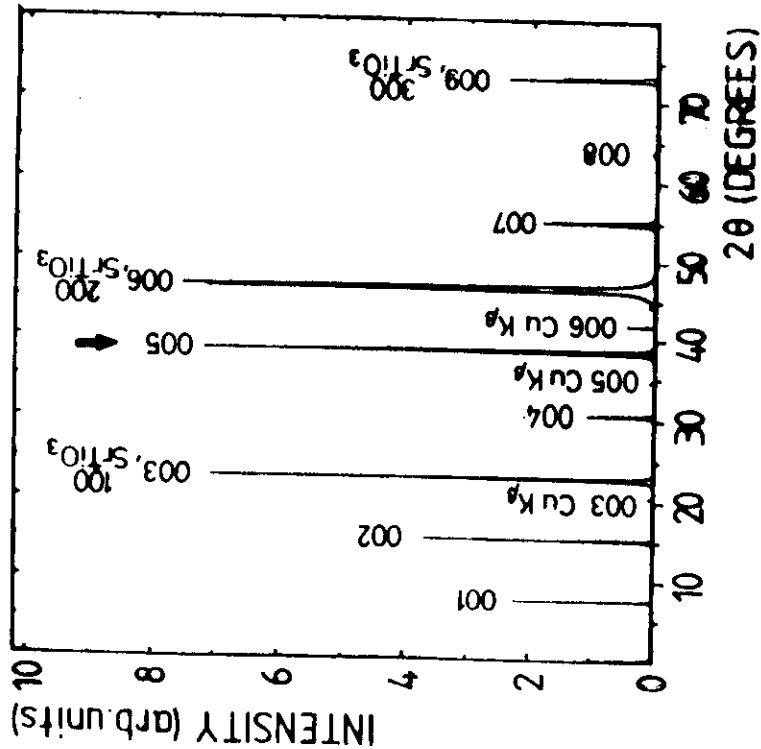


Rocking curve of the (005) peak.

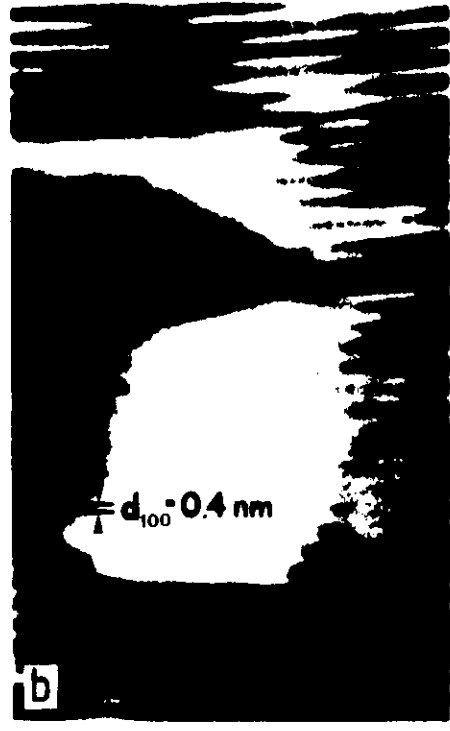
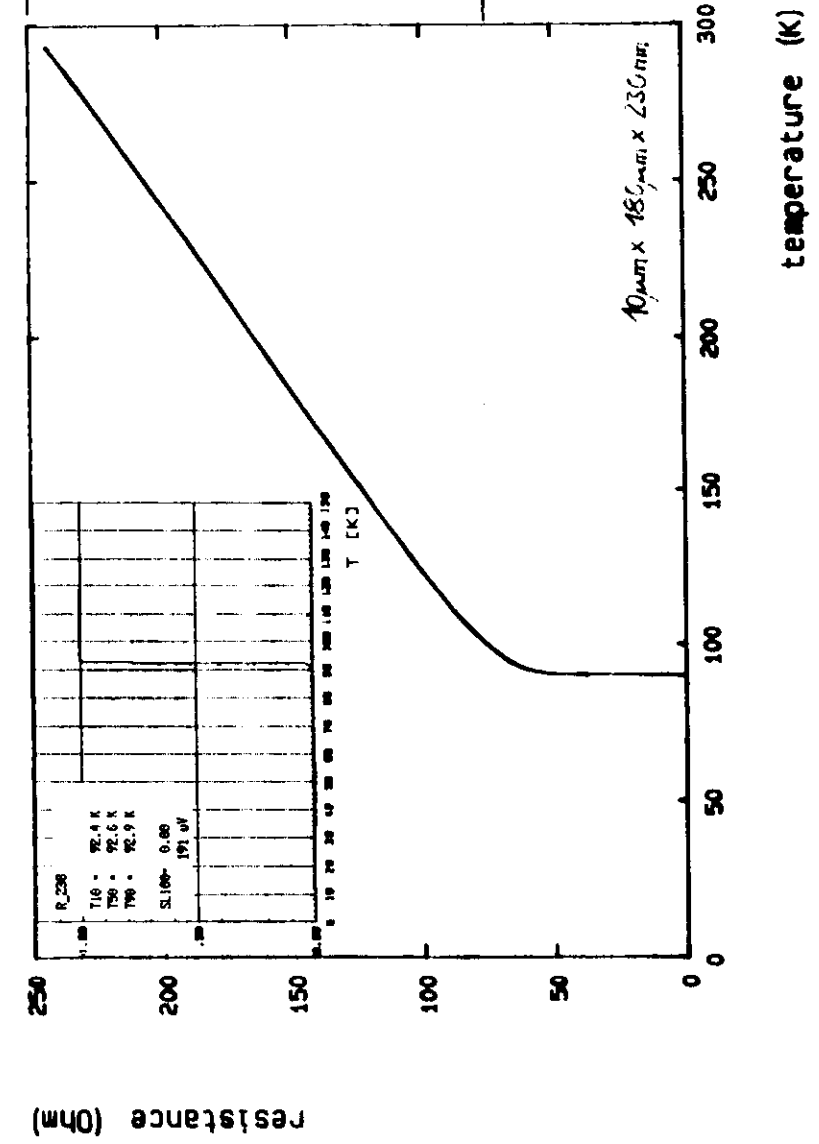
good superconductor:

$$2\theta = 38.55^\circ$$

$$\lambda_c = 11.67 \text{ \AA}$$



X-ray diffraction pattern of an $\text{V}_{0.9}\text{Ca}_{0.1}\text{O}_{7-x}$ thin film epitaxially grown on a $\langle 100 \rangle$ SrTiO_3 substrate.



YBaCu₃O_x thin film deposited by laser ablation

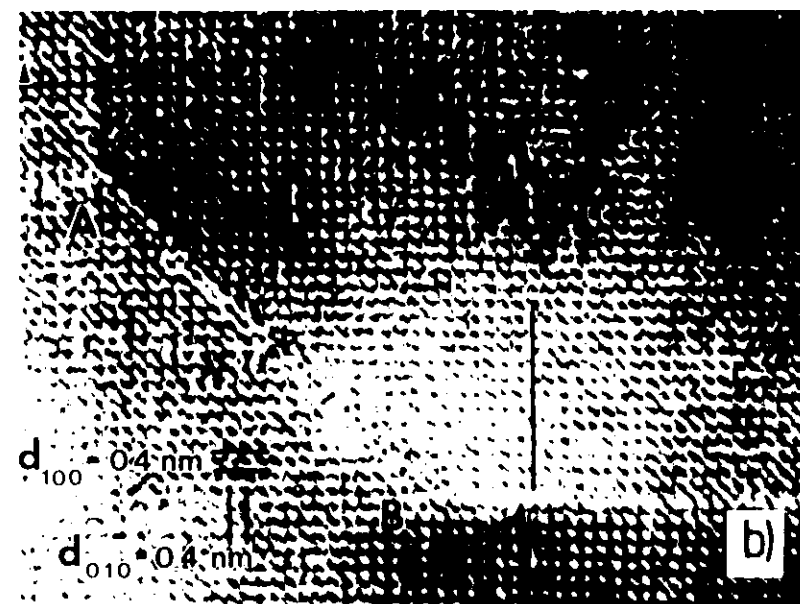
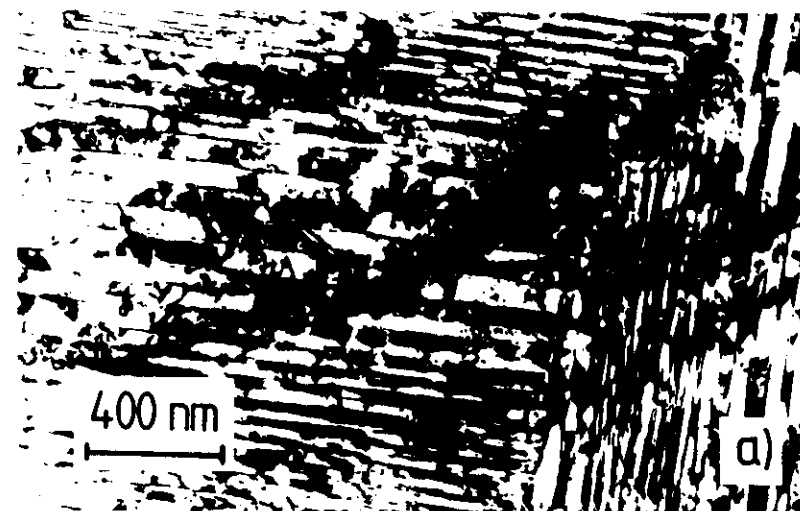
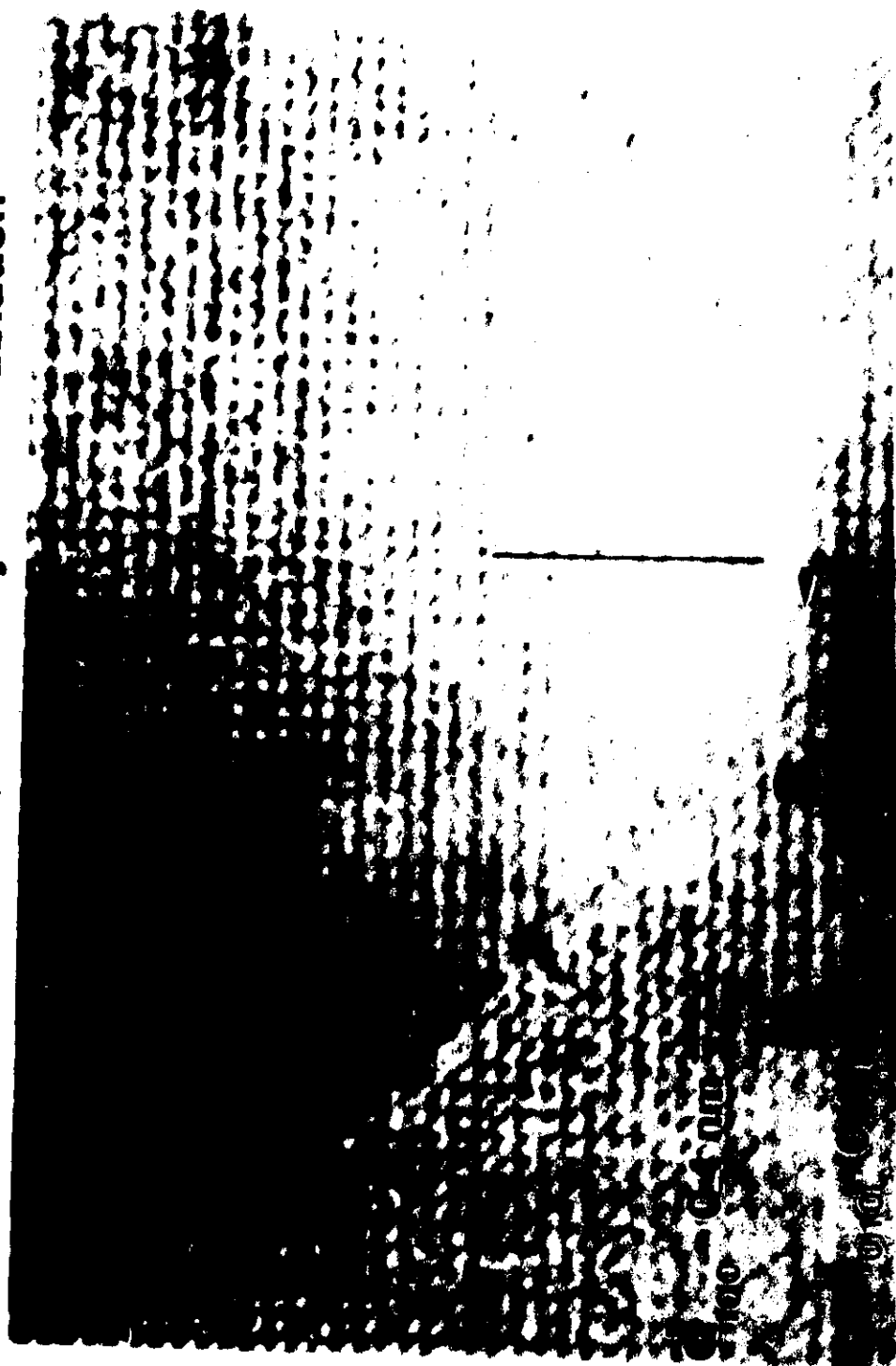
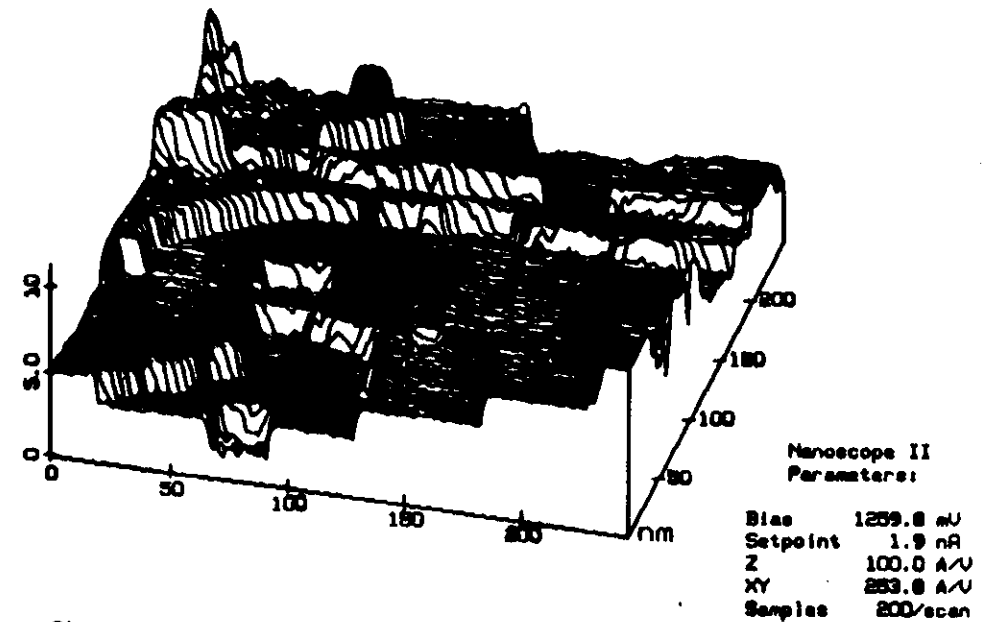
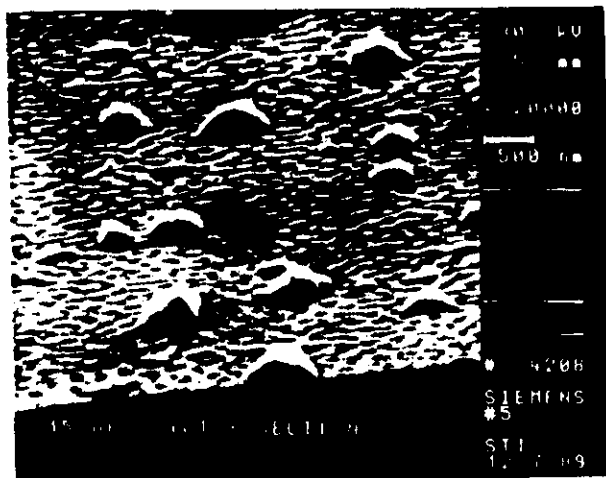
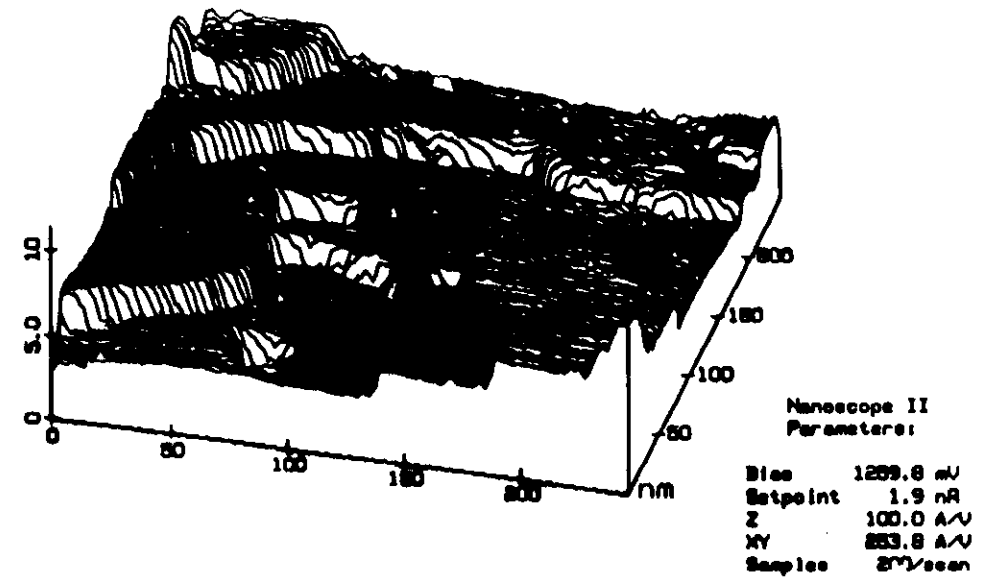
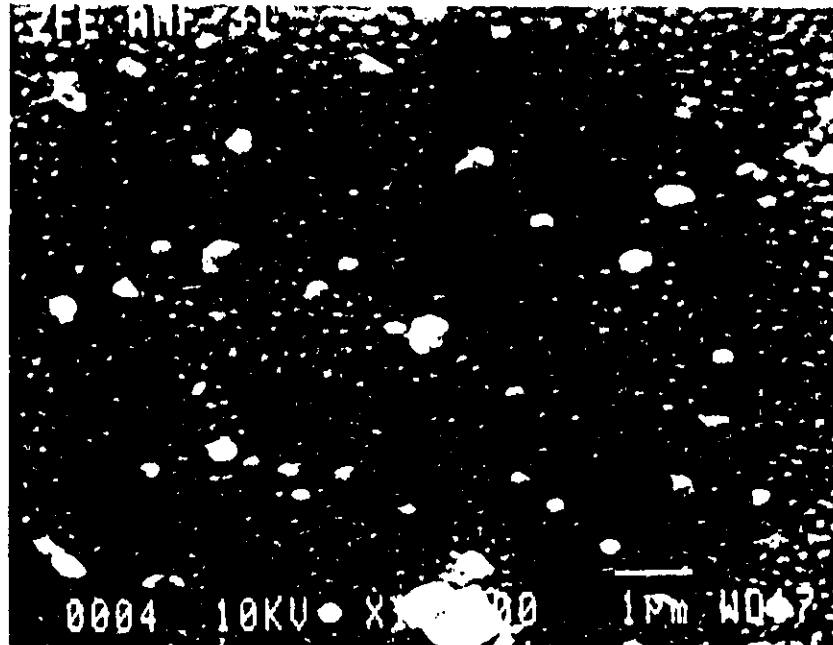


Fig. 4:

- a) Twin boundaries along the [110] direction in a laser deposited YBa₂Cu₃O_x film. The distance of two boundaries varies from 40 to 80 nm.
- b) High resolution transmission electron micrograph of an epitaxial film in the [001] pole. A stacking fault and a shift of the lattice by half of an unit cell can be seen.

Scanning Tunneling Microscopy of laser-evaporated YBaCuO thin films in air

(in collaboration with Prof. Dr. Kirschner, Institut für Atom- und Festkörperphysik der Freien Universität Berlin)



Clean YBaCuO in air
Data taken Fri May 26 10:24:00 1989
Buffer 5, Rotated 0°, XY axes (nm), Z axis (nm)